



IFW

Docket No.: 060188-0751

PATENT**IN THE UNITED STATES PATENT AND TRADEMARK OFFICE**

In re Application of : Customer Number: 20277  
Yoshiharu HIDAKA, et al. : Confirmation Number: 8259  
Application No.: 10/754,518 : Group Art Unit: 2814  
Filed: January 12, 2004 : Examiner: Thao X. Le  
:

For: SEMICONDUCTOR SUBSTRATE, METHOD FOR FABRICATING THE SAME, AND  
METHOD FOR FABRICATING SEMICONDUCTOR DEVICE

**INFORMATION DISCLOSURE STATEMENT**

Mail Stop Amendment  
Commissioner for Patents  
P.O. Box 1450  
Alexandria, VA 22313-1450

Dear Sir:

In accordance with the provisions of 37 C.F.R. 1.56, 1.97 and 1.98, the attention of the Patent and Trademark Office is hereby directed to the documents listed on the attached form PTO-1449. It is respectfully requested that the documents be expressly considered during the prosecution of this application, and that the documents be made of record therein and appear among the "References Cited" on any patent to issue therefrom.

This Information Disclosure Statement is being filed more than three months after the U.S. filing date AND after the mailing date of the first Office Action on the merits, but before the mailing date of a Final Rejection or Notice of Allowance.

**CERTIFICATION PARAGRAPH**

The undersigned certifies that each item of information contained in this Information Disclosure Statement was first cited in a communication from a foreign patent office in a counterpart foreign application not more than three months prior to the filing of this Information Disclosure Statement as described in 37 CFR 1.97(e)(1).

Each non-English language reference was cited in a corresponding foreign application search report and its relevance discussed therein. A copy of the foreign search report is attached for the Examiner's information.

Please charge any shortage in fees due in connection with the filing of this paper, including extension of time fees, to Deposit Account 500417 and please credit any excess fees to such deposit account.

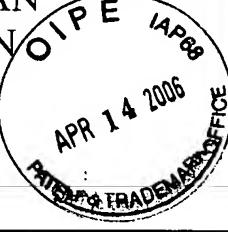
Respectfully submitted,

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<b>INFORMATION DISCLOSURE CITATION IN AN APPLICATION</b> (PTO-1449)			ATTY. DOCKET NO. <b>060188-0751</b>	SERIAL NO. <b>10/754,518</b>		
 <b>APPLICANT Yoshiharu HIDAKA, et al.</b>						
			FILING DATE <b>January 12, 2004</b>	GROUP <b>2814</b>		
<b>U.S. PATENT DOCUMENTS</b>						
EXAMINER'S INITIALS	CITE NO.	Document Number Number-Kind Code <sub>2</sub> ( <i>if known</i> )	Publication Date MM-DD-YYYY	Name of Patentee or Applicant of Cited Document		
	US	5,185,965	02/16/1993	Ozaki		
	US	2001/0036738 A1	11/01/2001	Hatanaka et al		
	US	2002/0164934 A1	11/07/2002	Honda		
	US					
	US					
	US					
	US					
<b>FOREIGN PATENT DOCUMENTS</b>						
EXAMINER'S INITIALS	CITE NO.	Foreign Patent Document Country Codes-Number +-Kind Codes ( <i>if known</i> )	Publication Date MM-DD-YYYY	Name of Patentee or Applicant of Cited Document	Pages, Columns, Lines Where Relevant Figures Appear	Translation Yes      No
		DE 43 31 727 A1	03/24/1994	DAITO SHOJI CO., LTD.; EMTEC CO.		GERMAN (w/ English Abstract)
		JP 2000-082688	03/21/2000	MITSUBISHI MATERIALS SILICON CORP.		JAPAN (w/ English Abstract)
<b>OTHER ART</b> (Including Author, Title, Date, Pertinent Pages, Etc.)						
EXAMINER'S INITIALS	CITE NO.	Include name of the author (in CAPITAL LETTERS), title of the article (when appropriate), title of the item (book, magazine, journal, serial, symposium, catalog, etc.), date, page(s), volume-issue number(s), publisher, city and/or country where published.				
EXAMINER			DATE CONSIDERED			

\*EXAMINER: Initial if reference considered, whether or not citation is in conformance with MPEP 609. Draw line through citation if not in conformance and not considered.

Include copy of this form with next communication to applicant.

1 Applicant's unique citation designation number (optional). 2 Applicant is to place a check mark here if English language Translation is attached.